FOR IMMEDIATE RELEASE

HORIBA Semiconductor Introduces the IR-400 end point monitor with Multi-Gas option

SUNNYVALE, CA June 28th, 2017 – HORIBA Semiconductor, global leader in Process Metrology and Control Components, introduces the IR-400 monitor, now with a Multi-Gas option. The IR-400 can detect trace amounts of cleaning gases such as NF3, SiF4, CF4 and WF6 and is now available with on-board gas type selection supporting a variety of cleaning gases.

The IR-400 uses tuned NDIR to detect a variety of gases in the process foreline, enabling tighter control over chamber clean process steps. The technology allows users to accurately and repeatably monitor the concentration of cleaning gases, enabling more effective management of chamber clean cycle times, and reduced overall operating costs.

"The IR-400 leverages established HORIBA absorption technology and offers users an innovative way to improve their process efficiencies", said Troy Freeman, Semiconductor Co-Segment Leader at HORIBA Semiconductor.

HORIBA technologies for dry process monitoring are used globally for critical process monitoring and control and the new IR-400 with Multi-Gas capability represents the latest in applications-driven technology development that supports improved process control in the Semiconductor Industry.

HORIBA Semiconductor, part of HORIBA INSTRUMENTS, INC., headquartered in the United States, provides an extensive array of instruments and solutions for applications across a broad range of Semiconductor processes. HORIBA Semiconductor is a world leader in the measurement and control of critical process chemistries. Our instruments are found in equipment and facilities worldwide and HORIBA is a recognized technology leader in the Semiconductor industry.

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